



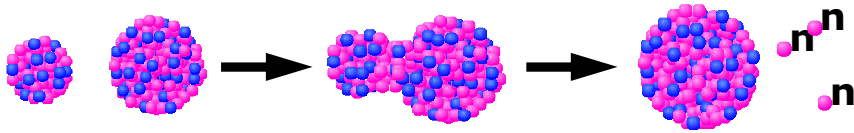
Targets for SHE experiments with intense beams



GSI Nuclear Chemistry Group □ GSI Target Laboratory
Workshops GSI + JGU □ JGU Nuclear Chemistry

- SHE production with actinide targets
- Target production - Molecular Plating
- New (100-mm) target wheel @ TASCA
- Target development

SHE production with actinide targets



- E114 $^{244}\text{Pu}(^{48}\text{Ca}, xn)$
- E115 $^{243}\text{Am}(^{48}\text{Ca}, xn)$
- E116 $^{248}\text{Cm}(^{48}\text{Ca}, xn)$
- E117 $^{249}\text{Bk}(^{48}\text{Ca}, xn)$
- E119 $^{249}\text{Bk}(^{50}\text{Ti}, xn)$
- E120 $^{248}\text{Cm}(^{54}\text{Cr}, xn)$
- E120 $^{249}\text{Cf}(^{50}\text{Ti}, xn)$

Target production technique:

- Chemical purification prior to deposition
- Recovery and chemical purification of used target material
- Small and simple set-up
- Components easy to replace in order to avoid cross-contamination

Target thickness:.....500 $\mu\text{g}/\text{cm}^2$

Electrochemical deposition:

Molecular Plating

ARTESIA target wheel

O-Ring, Viton (20 x 1.3 mm)

Backing foil (Ti/2 μm)
Active area: 1.4 cm^2

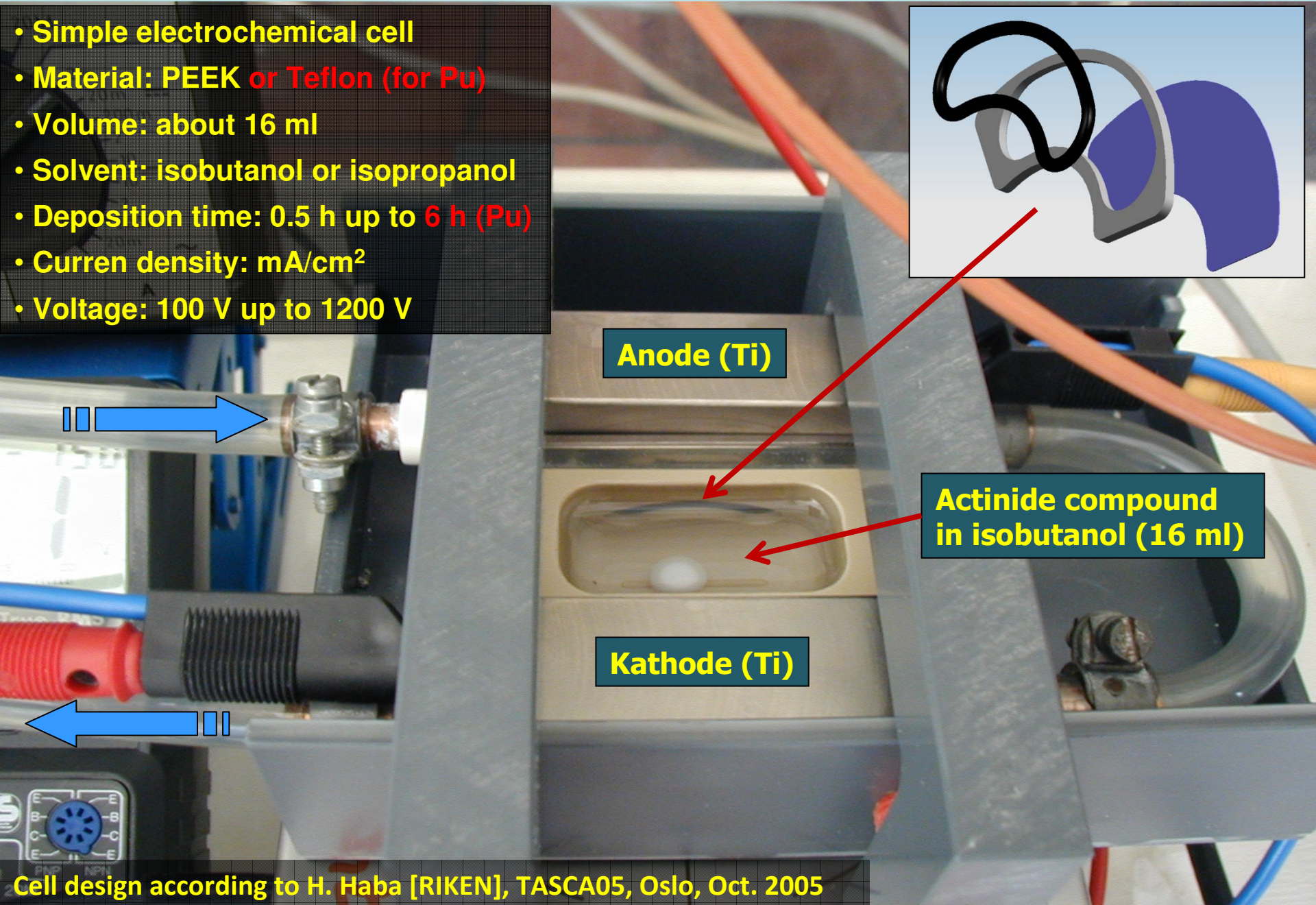
Supporting frame
(Al 1.0 mm)

Beam spot: 6 mm

Material consumption:
2.1 mg per wheel @ 500 $\mu\text{g}/\text{cm}^2$

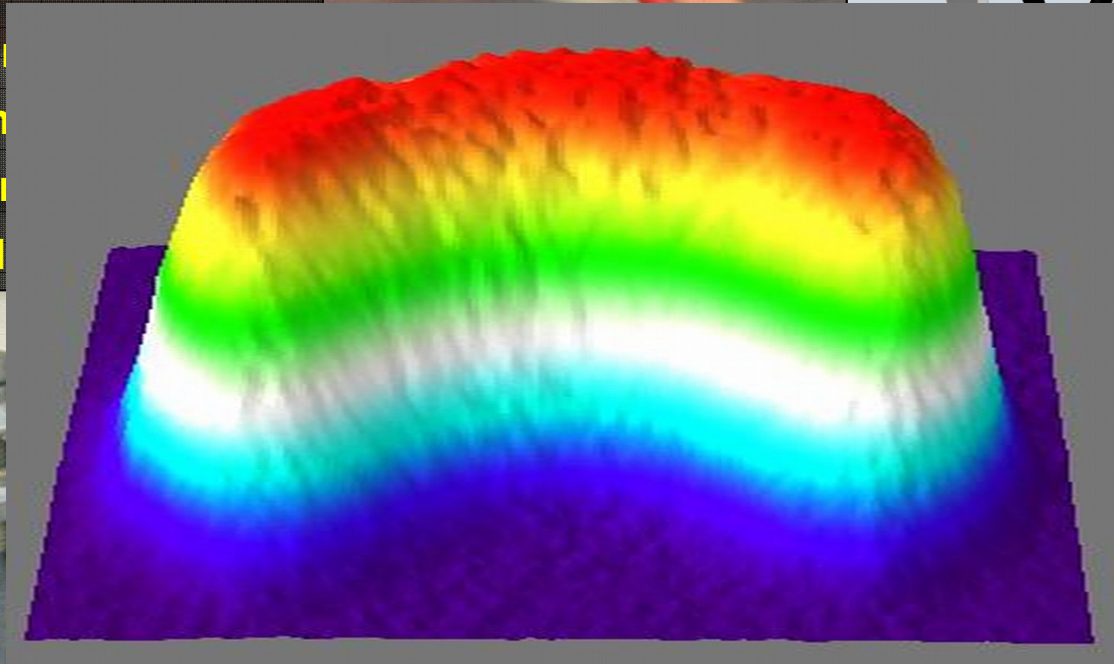
Actinide deposition by Molecular Plating

- Simple electrochemical cell
- Material: PEEK or Teflon (for Pu)
- Volume: about 16 ml
- Solvent: isobutanol or isopropanol
- Deposition time: 0.5 h up to 6 h (Pu)
- Current density: mA/cm²
- Voltage: 100 V up to 1200 V



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Compound
ol (16 ml)

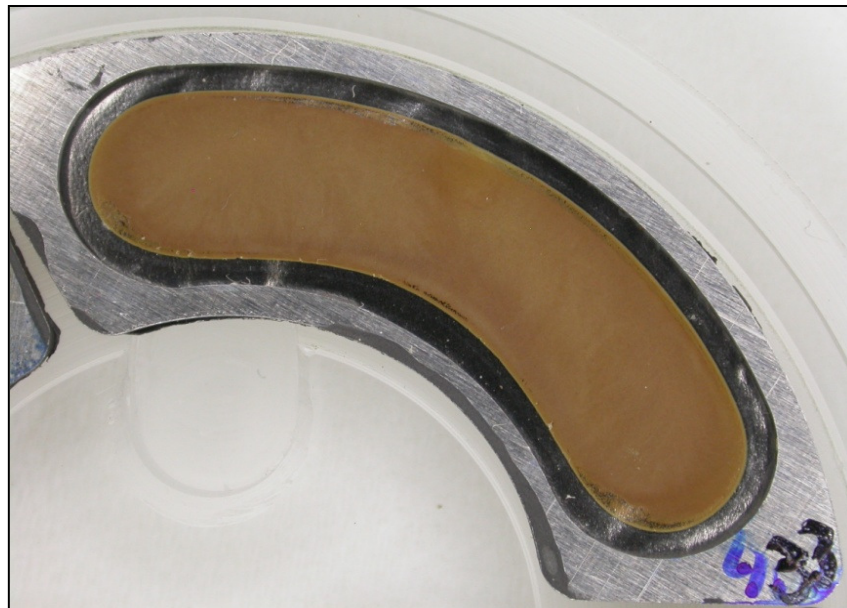
Deposition yield: up to 90%
Target thickness: mg/cm² possible
Target homogeneity: radiographic imaging

Deposition of Pu and Cm by Molecular Plating

Deposition conditions for Pu:

Solvent.....Isobutanol
Plating time.....6 h
Voltage.....150 – 200 V
Current density.....1.4 mA/cm²
Stirring at.....1200 U/min
Temperature.....15 °C

E114 □ ²⁴⁴Pu(⁴⁸Ca,xn)

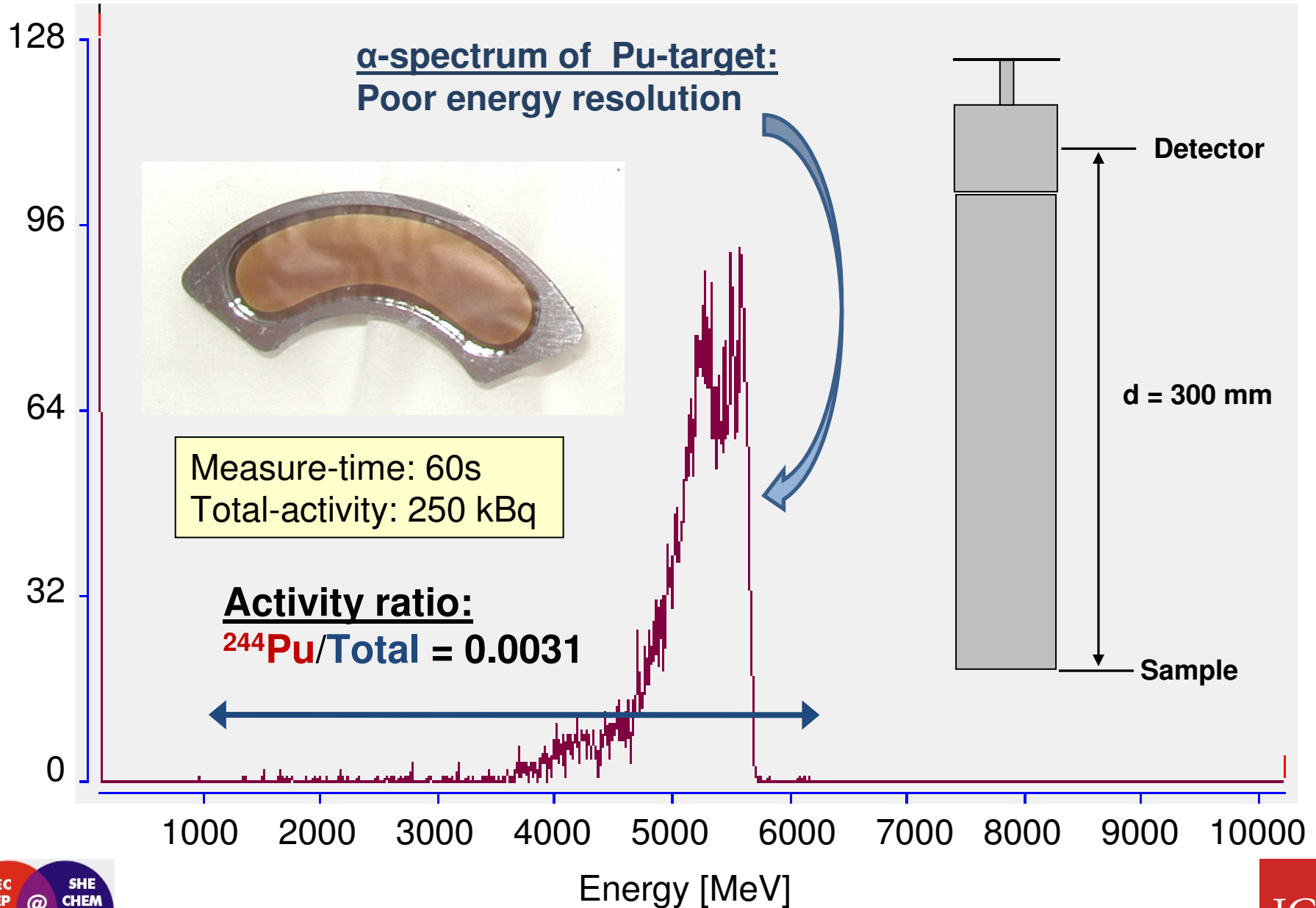


Deposition conditions for Cm:

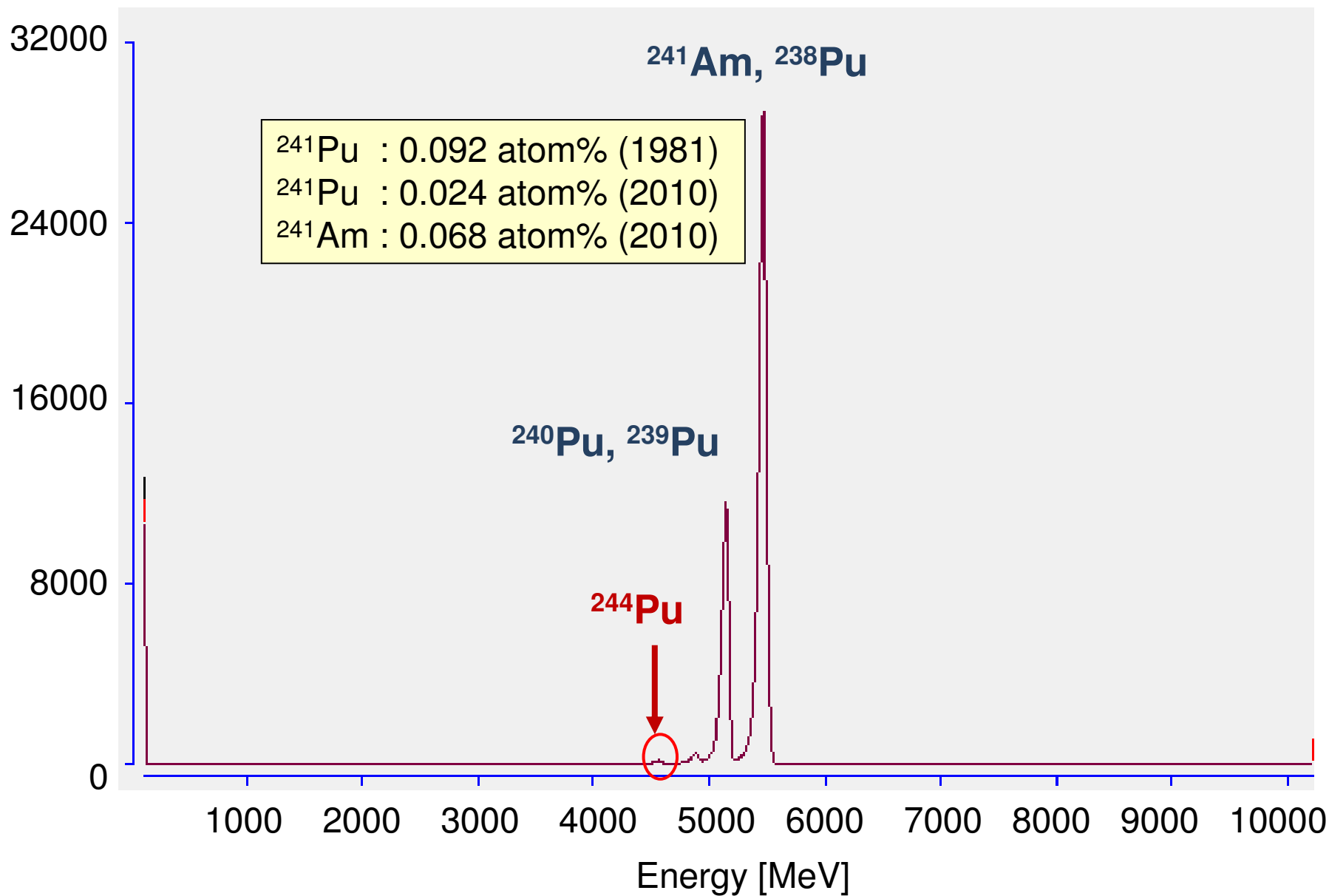
Solvent.....Isobutanol
Plating time.....3 h
Voltage.....150 – 300 V
Current density.....0.7 mA/cm²
Stirring at.....1200 U/min
Temperature.....15 °C

E116 □ ²⁴⁸Cm(⁴⁸Ca,xn)

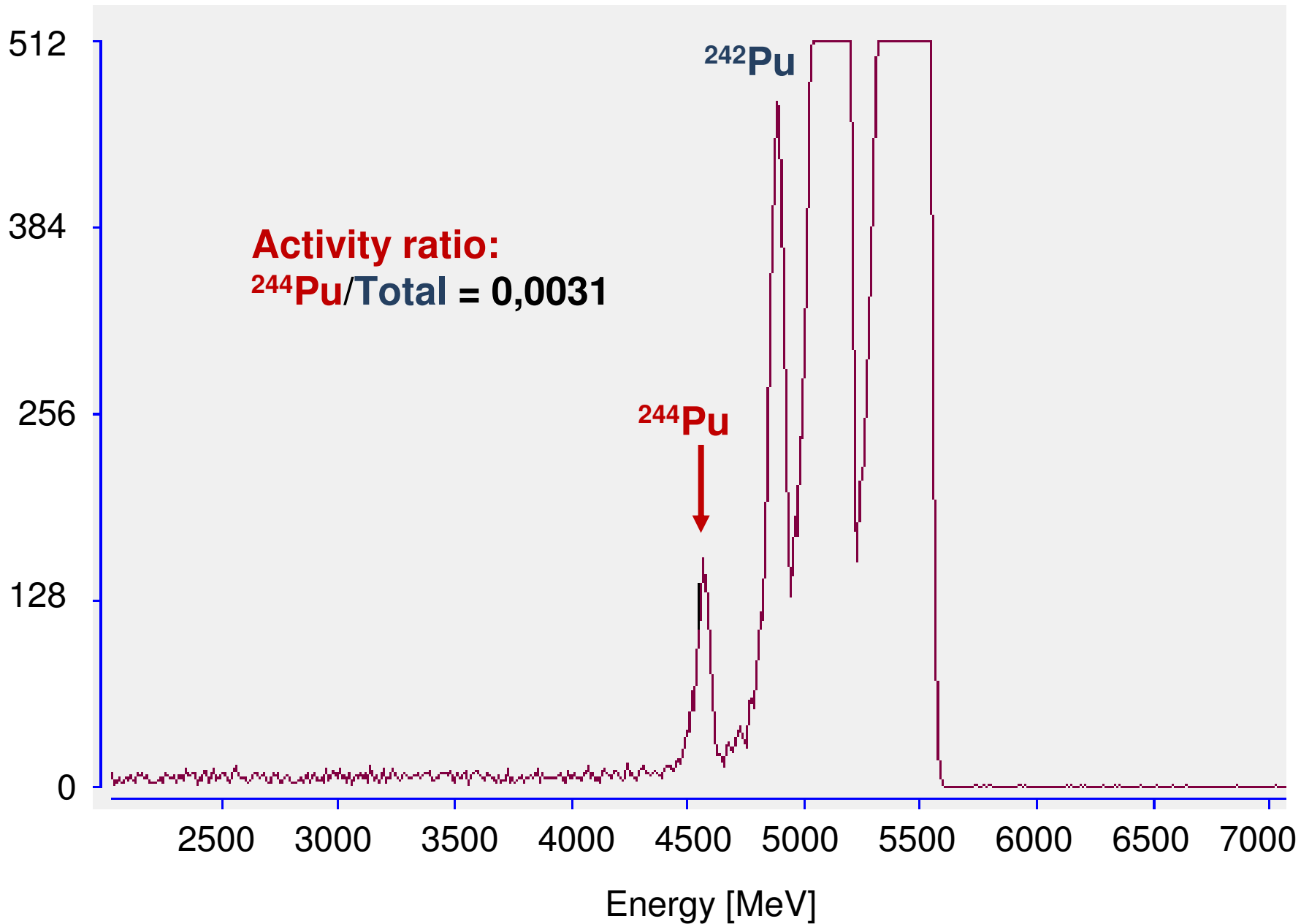
Direct yield measurement: α -particle spectroscopy



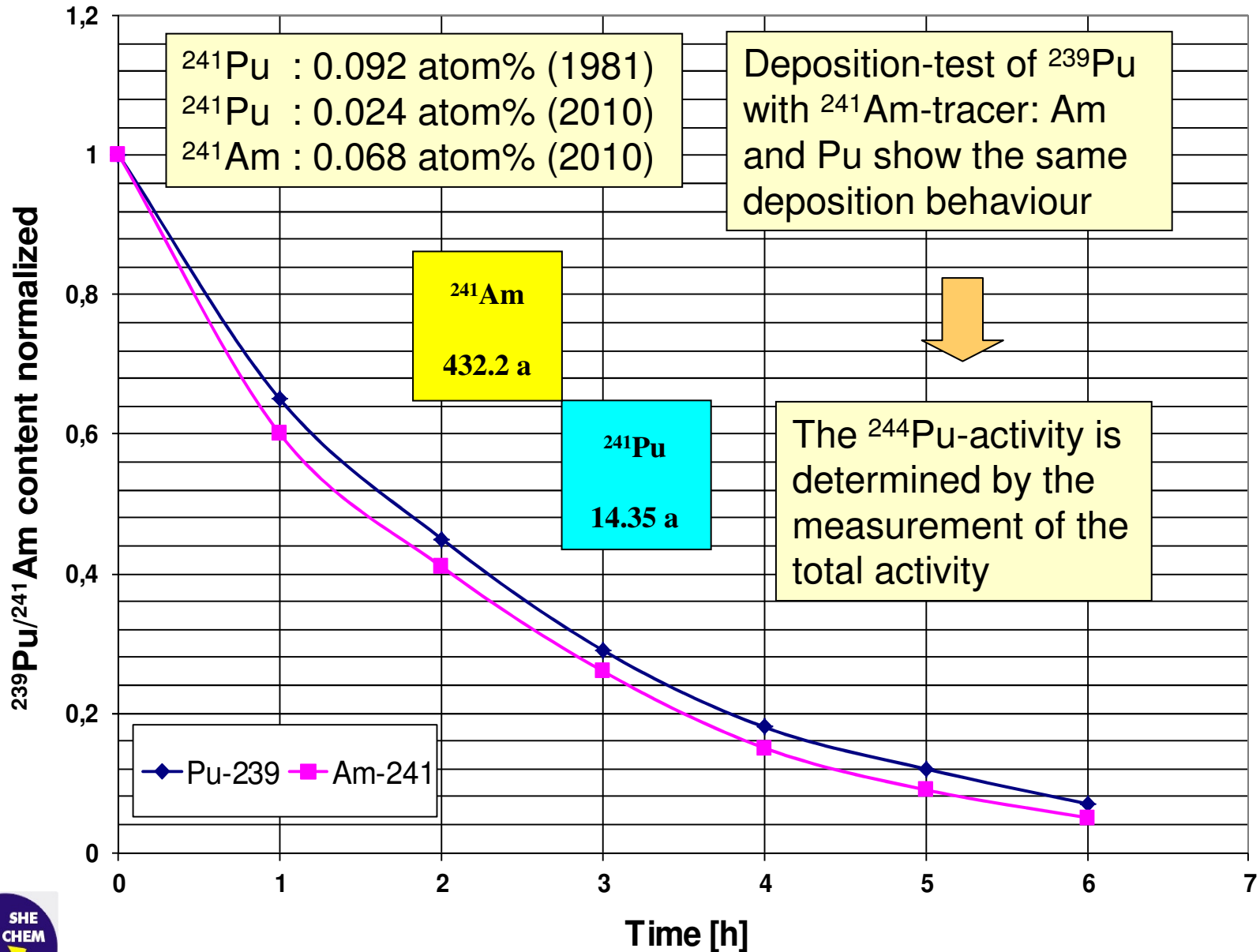
^{244}Pu stock solution



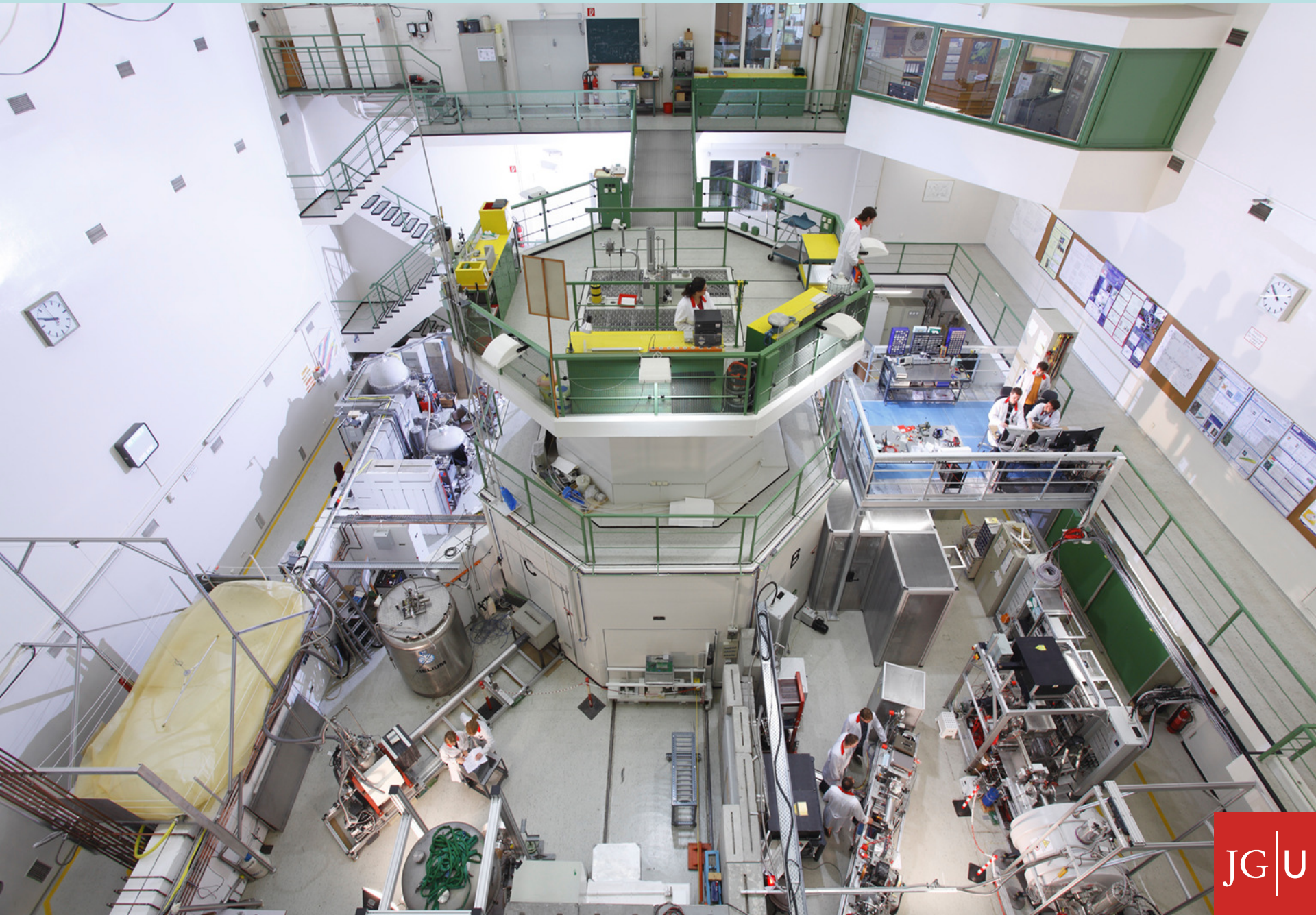
^{244}Pu stock solution



Simultaneous deposition of ^{239}Pu and ^{241}Am



Indirect yield measurement: NAA @ TRIGA Mainz



Indirect yield measurement: NAA of Pu and Cm

Irradiation of 1 ml of supernatant solution after deposition

^{249}Bk

320 d

b⁻ 0.1
g 327, 308

^{248}Cm

3.4×10^5 a

a 5.078, 5.035

^{249}Cm

64 min

b⁻ 0.9
g 634, 560, 369

^{245}Am

2.05 h

b⁻ 0.9
g 253

^{244}Pu

8×10^7 a

a 4.589; 4.546

^{245}Pu

10.5 h

b⁻ 0.9; 1.2
g 327; 560; 308

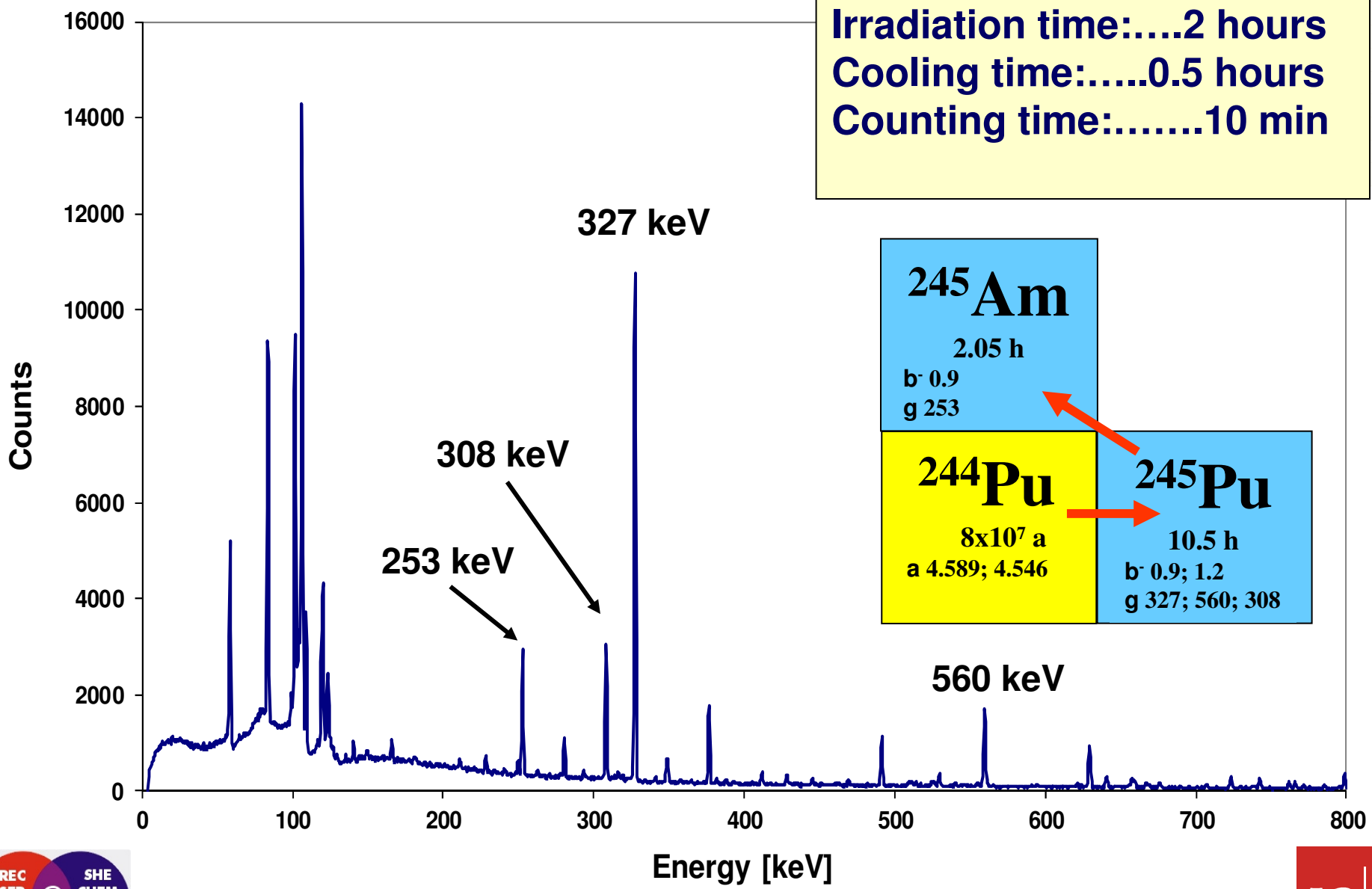
T Irradiation: 2 h

□ thermal: $7 \times 10^{11} \text{ cm}^{-2} \text{ s}^{-1}$

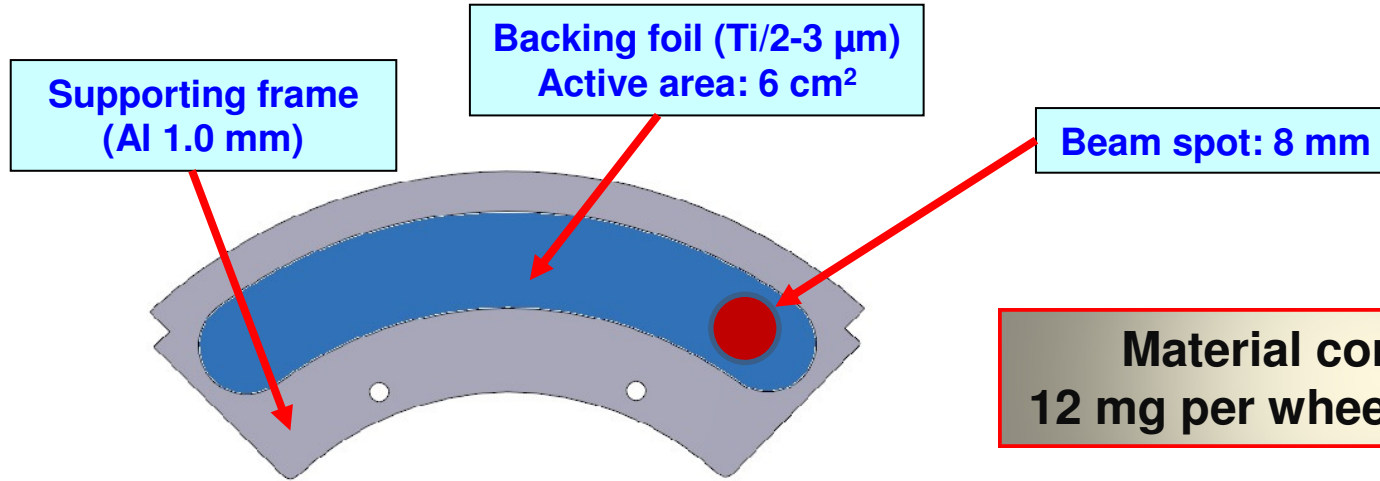
1

□ -spectrum of irradiated ^{244}Pu solution (1 ml / 10 μg)

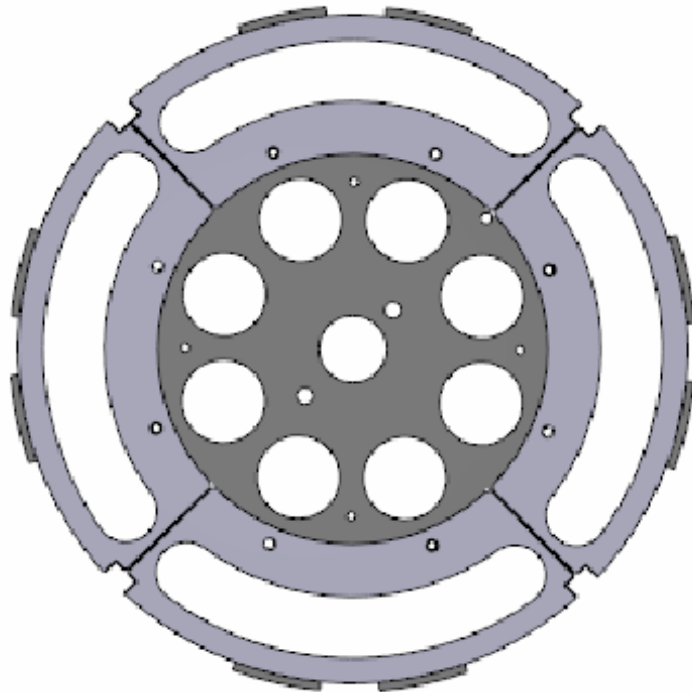
Irradiation time:....2 hours
Cooling time:.....0.5 hours
Counting time:.....10 min



New (100-mm) target wheel



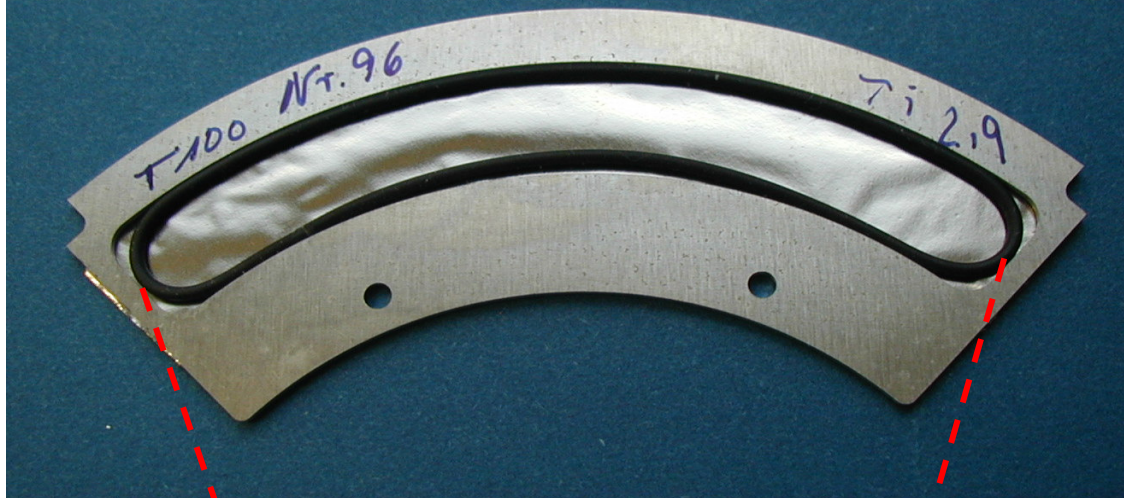
**Material consumption:
12 mg per wheel @ 500 $\mu\text{g}/\text{cm}^2$**



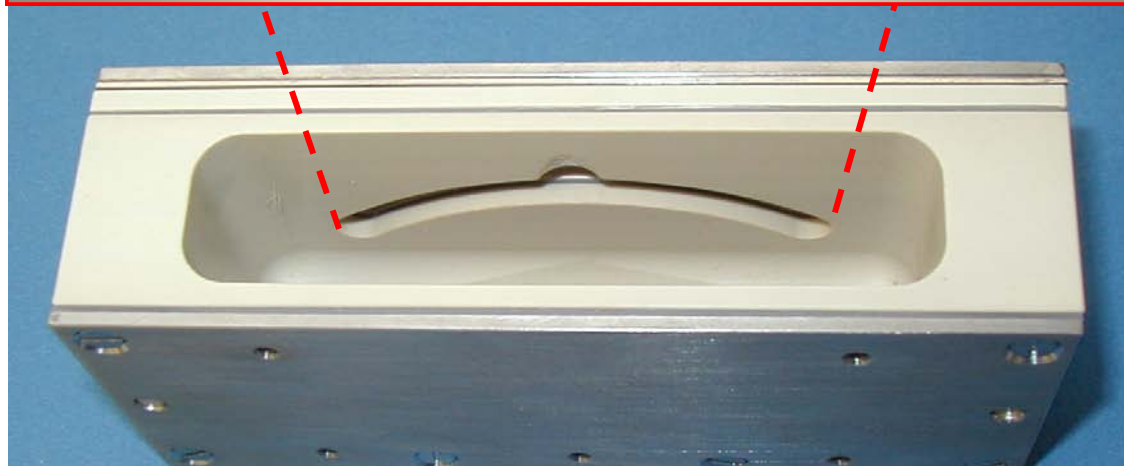
	ARTESIA	New wheel
Material	2 mg	12 mg
Target area	1.4 cm^2	6 cm^2
Beam spot	6 mm	8 mm
Gain factor		1.8
Intensity	0.5 μA	1.0 μA
Gain factor		2

New (100-mm) target wheel

Supporting frame (Al 1.0 mm) with Ti-backing foil (2.9 μm)



Deposition of Gd tested
First targets irradiated with low beam intensity



Electrochemical cell assembly (26 ml volume)

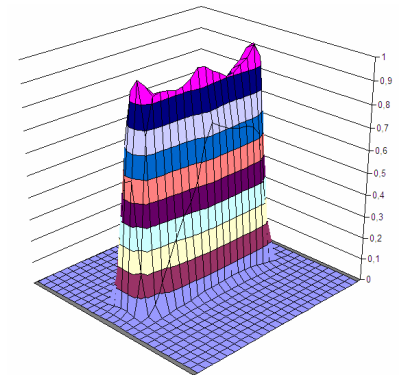
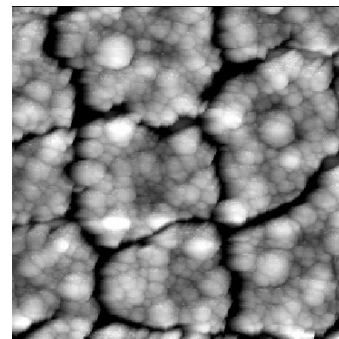
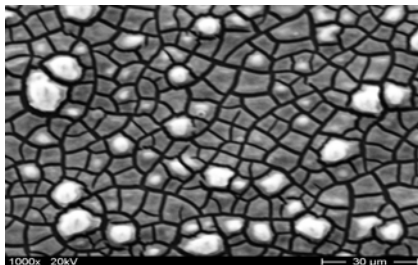
Target development

Alternative backing materials:

- Beryllium
- Diamond-like carbon (DLC)
- Polyimid-foil covered with metallic layer

Target layer characterization:

- Yield: α -particle spectroscopy / Neutron activation analysis
- Layer homogeneity: Radiographic imaging
- Morphology: SEM and AFM

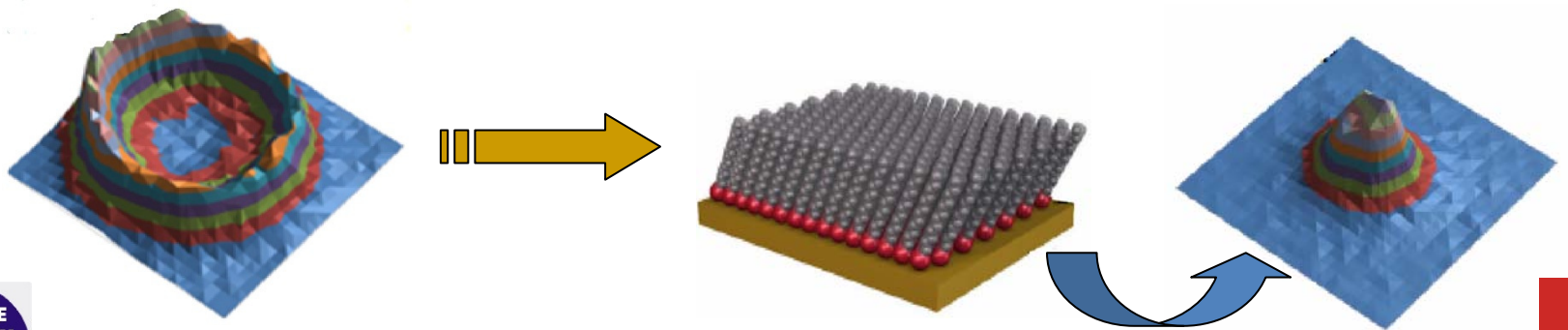


- More detailed understanding of the deposition process
[Vascon et al., submitted to NIM A]

Target development

Alternative target production techniques

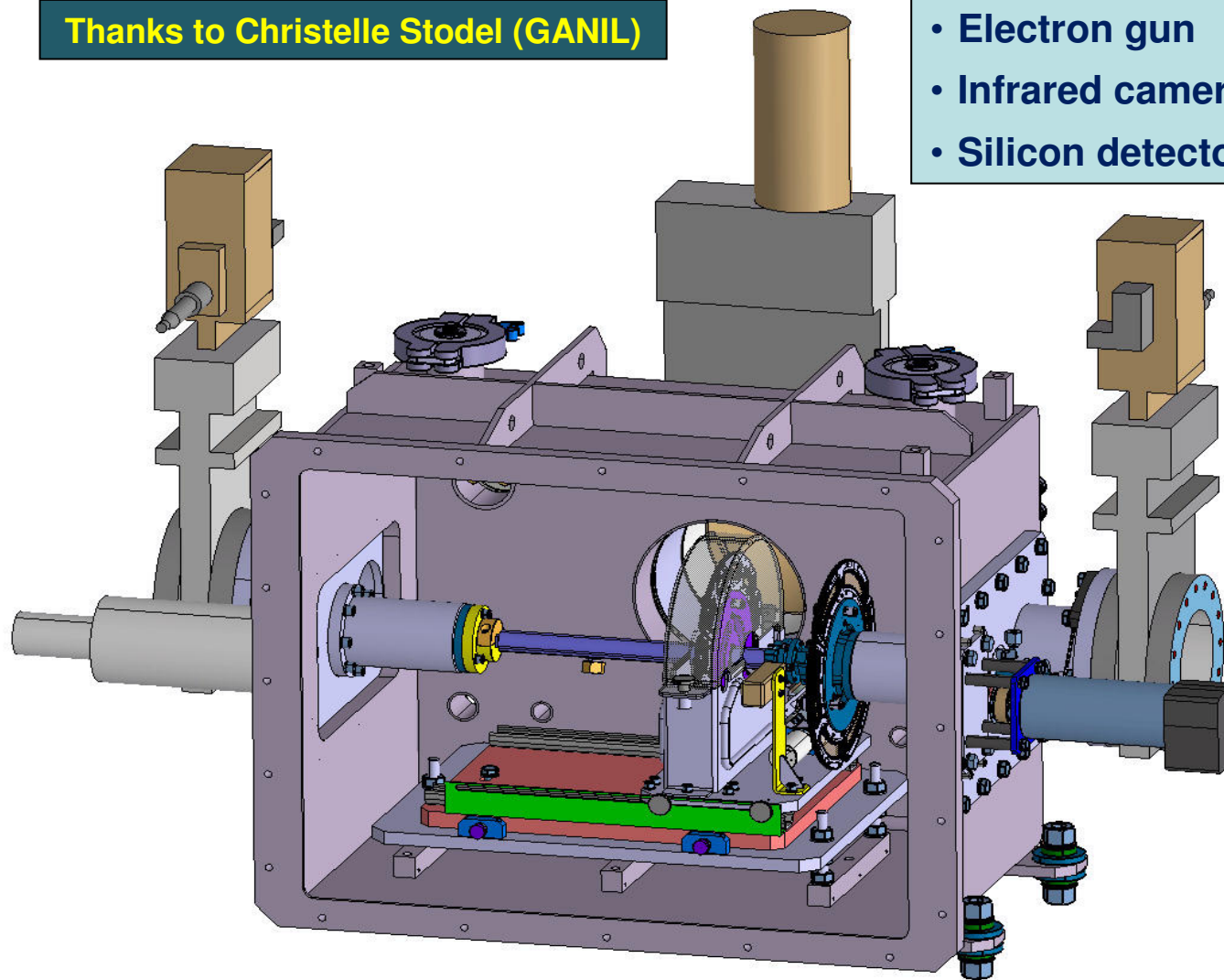
- **Polymer-assisted deposition (PAD):** Metal-oxide mixed with polymer solution. Spin-coating of silicon substrate with metal-organic film. Target thickness up to $600 \mu\text{g}/\text{cm}^2$ possible. No irradiation tests with actinide elements so far
[Garcia et al., Nucl. Instr. Meth. Phys. Res. A613 (2010) 396]
- **Superhydrophobic surfaces:** Modification of a substrate with self-assembled monolayer of alkyl chains. Homogenous deposition of metal-oxide/nitrate from aqueous solution by simple evaporation of single drops [D. Renisch, Diploma Thesis, JGU (2010)]



Design of the actinide prototype target chamber @ GANIL

Thanks to Christelle Stodel (GANIL)

- Electron gun
- Infrared camera
- Silicon detector



Irradiation tests with up to $1 \mu\text{A}$ ^{48}Ca -beam possible